

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S10	95	(US-20060171848-\$ or US-20050284570-\$ or US-20050011611-\$ or US-20040007326-\$ or US-20030197167-\$ or US-20020161557-\$ or US-20030029834-\$ or US-20030000922-\$ or US-20020026251-\$ or US-20020078770-\$ or US-20020048019-\$ or US-20020000631-\$ or US-20020020802-\$ or US-20010015175-\$ or US-20010014520-\$ or US-20030132198-\$ or US-20020137266-\$ or US-20040021094-\$).did. or (US-7149643-\$ or US-6889568-\$ or US-6902646-\$ or US-6835275-\$ or US-6849470-\$ or US-6827870-\$ or US-6830650-\$ or US-6741945-\$ or US-6759253-\$ or US-6716301-\$ or US-6747290-\$ or US-6738722-\$ or US-6653852-\$ or US-6632321-\$ or US-6580091-\$ or US-6673636-\$ or US-6547458-\$ or US-6531711-\$ or US-6620631-\$ or US-6576922-\$ or US-6485988-\$ or US-6462328-\$ or US-6432260-\$ or US-6508990-\$ or US-6492277-\$ or US-6333544-\$).did. or (US-6472240-\$ or US-6306594-\$ or US-6287888-\$ or US-6326794-\$ or US-6265241-\$ or US-6232236-\$ or US-6127237-\$ or US-6113733-\$ or US-6281535-\$ or US-6096232-\$ or US-6131580-\$ or US-6052185-\$ or US-6075909-\$ or US-5869877-\$ or US-5846883-\$ or US-6060329-\$ or US-5801386-\$ or US-5989929-\$ or US-5896196-\$ or US-5744796-\$ or US-5733820-\$ or US-5871658-\$ or US-5683538-\$ or US-	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/21 13:19

		5576630-\$ or US-5576629-\$ or US-5821548-\$ or US-5571366-\$).did. or (US-5482684-\$ or US-5779918-\$ or US-5468665-\$ or US-5451784-\$ or US-5444637-\$ or US-5409562-\$ or US-5212118-\$ or US-5472508-\$ or US-5206506-\$ or US-4951602-\$ or US-4849629-\$ or US-5444259-\$ or US-4831267-\$ or US-5002631-\$ or US-4888199-\$ or US-6097157-\$ or US-6849191-\$ or US-5846885-\$ or US-5565681-\$ or US-5393986-\$ or US-5633616-\$ or US-5091655-\$ or US-6806101-\$).did. or (JP-10074481-\$).did.				
S11	2	"20050115673"	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/21 14:35
S12	42	S10 and ((silicon adj oxide) or "SiO.sub.2")	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/21 14:48
S13	3	S10 and (((silicon adj oxide) or "SiO.sub.2") same (aluminum near6 electrode \$2))	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/21 15:05
S14	8	S10 and (((silicon adj oxide) or "SiO.sub.2") and (aluminum near6 electrode \$2))	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/21 15:05
S15	480	plasma and (wafer\$2 near4 (monitor\$4 measure\$5)) and (aluminum near5 electrode\$2)	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/21 15:16
S16	251	S15 and @ad<"20020326"	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/21 15:16
S17	33	S16 and (156/345.\$2 118/715-733).ccls.	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/21 15:17
S18	114	S16 and ("216"/\$ "438"/\$).ccls.	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/21 15:23
S19	99	S18 not S17	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/21 15:23
S20	137	S16 not S18	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/21 15:57

S21	119	S20 not S17	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/21 15:57
S22	1	plasma and (wafer\$2 near4 (monitor\$4 measure\$5)) and (aluminum near5 electrode\$2)	EPO; JPO; DERWENT	OR	OFF	2008/08/21 16:16
S23	357	(plasma same (monitor\$4 measure\$5 sens\$4)) and (aluminum near5 electrode \$2) and (ion\$2 near4 energy)	US-PGPUB; USPAT	OR	OFF	2008/08/21 16:19
S24	208	S23 and @ad< "20020326"	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/21 16:19
S25	170	S24 not S16	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/21 16:20
S26	14	S25 and (156/345.24,345.28 315/111.\$2).ccls.	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/21 16:20
S27	833	plasma and ((monitor\$4 measure\$5 sens\$4) with (ion \$2 near4 energy)) and (electrode\$2 near& (stack\$4 layer\$3 plural\$4))	US-PGPUB; USPAT	OR	OFF	2008/08/21 17:35
S28	192	plasma and (((monitor\$4 measure\$5) with (ion\$2 near4 energy)) same (electrode\$2 sensor\$3near& (stack\$4 layer\$3 plural\$4)))	US-PGPUB; USPAT	OR	OFF	2008/08/21 17:37
S29	80	S28 and @ad< "20020326"	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/21 17:37
S30	84	plasma and (etch\$3 near8 (trench\$3 aspect deep)) and ((monitor\$4 measure\$5 sens \$4) with (ion\$2 near4 energy)) and (electrode\$2 near& (stack\$4 layer\$3 plural\$4))	US-PGPUB; USPAT	OR	OFF	2008/08/21 18:07
S31	27	S30 and @ad< "20020326"	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/21 18:07
S32	18	S31 not S29	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/21 18:07

S33	80	plasma and (etch\$3 near8 (trench\$3 aspect deep)) and ((monitor\$4 measure\$5 sens\$4) with (ion\$2 near4 energy)) and (electrode\$2 near& aluminum)	US-PGPUB; USPAT	OR	OFF	2008/08/21 18:22
S34	0	S33 not S30	US-PGPUB; USPAT	OR	OFF	2008/08/21 18:22
S35	4	S30 not S33	US-PGPUB; USPAT	OR	OFF	2008/08/21 18:22
S36	836	156/345.24,345.28.ccls.	US-PGPUB; USPAT	OR	OFF	2008/08/21 18:24
S37	332	S36 and @ad< "20020326"	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/21 18:25
S38	8	S37 and (wafer\$2 near6 (monitor\$5 sens\$4 measure\$5)).ti.	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/21 18:26
S39	508	(wafer\$2 near6 (monitor\$5 sens\$4 measure\$5)).ti.	US-PGPUB; USPAT	OR	OFF	2008/08/21 18:29
S40	260	S39 and @ad< "20020326"	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/21 18:29
S41	136	S39 and @ad< "20020326" and etch\$3	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/21 18:30
S42	3	"6485988".pn. "6741945".pn. "5801386".pn.	USPAT	OR	OFF	2008/08/22 08:55
S43	5479	(wafer\$2 near6 (monitor\$5 sens\$4 measure\$5)) and aluminum and ((silicon adj oxide) or "SiO.sub.2")	US-PGPUB; USPAT	OR	OFF	2008/08/22 09:02
S44	6176	(wafer\$2 near6 (monitor\$5 sens\$4 measure\$5 charg\$3)) and aluminum and ((silicon adj oxide) or "SiO.sub.2")	US-PGPUB; USPAT	OR	OFF	2008/08/22 09:02
S45	2940	S44 and @ad< "20020326"	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/22 09:03
S46	836	156/345.24,345.28.ccls.	US-PGPUB; USPAT	OR	OFF	2008/08/22 09:03
S47	332	S46 and @ad< "20020326"	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/22 09:03
S48	23	S45 and S47	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/22 09:03

S49	145	S45 and (energy near5 (analyze\$4 measure\$5 monitor\$4))	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/22 09:09
S50	5	S45 and ((ion\$2 near5 energy) near5 (analyze\$4 measure\$5 monitor\$4))	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/22 09:14
S51	21	(US-20050115673-\$ or US-20020020802-\$ or US-20010014520-\$ or US-20020048019-\$).did. or (US-6576922-\$ or US-5444637-\$ or US-5451784-\$ or US-6448094-\$ or US-5315145-\$ or US-6553277-\$ or US-5565681-\$ or US-6326794-\$ or US-5824602-\$ or US-6008132-\$ or US-5665253-\$ or US-6125529-\$ or US-5801386-\$ or US-6485988-\$ or US-6741945-\$ or US-6759253-\$).did. or (JP-10074481-\$).did.	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/22 09:18
S52	9	S51 and aluminum and ((silicon adj oxide) or "SiO.sub.2")	US-PGPUB; USPAT	OR	OFF	2008/08/22 09:19
S53	5	S51 and aluminum and ((silicon adj oxide) or "SiO.sub.2") and (ion\$2 near4 energy)	US-PGPUB; USPAT	OR	OFF	2008/08/22 09:22
S54	304	plasma and (((mass adj analyze\$4) or (ion\$2 near5 energy)) near6 (control\$4 measure\$4 monitor\$4))and (aluminum near6 (electrode \$2 or sensor\$2 antenna\$4)) and ((silicon adh oxide) or "SiO.sub.2")	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/22 10:05
S55	183	S54 and @ad<"20020326"	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/22 10:06
S56	173	plasma and (((mass adj analyze\$4) or (ion\$2 near5 energy)) near6 (control\$4 measure\$4 monitor\$4))and (aluminum near6 (electrode \$2 or sensor\$2 antenna\$4)) and ((silicon adj oxide) or "SiO.sub.2")	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/22 10:10
S57	109	S56 and @ad<"20020326"	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/22 10:10

S58	2	S51 and (pattern\$4 near6 ("sio.sub.2" or (silicon adj oxide\$2)))	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/22 10:19
S59	0	loewnhardt.in. and applied. as.	USPAT	OR	OFF	2008/08/22 10:25
S60	0	loewnhardt.in. and applied. as.	US-PGPUB; USPAT	OR	OFF	2008/08/22 10:25
S61	37	loewenhardt.in. and applied. as.	USPAT	OR	OFF	2008/08/22 10:25
S62	37	S61 and ad< "20020326" and plasma	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/22 10:26
S63	37	S61 and ad< "20020326"	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/22 10:26
S64	8	"6576922".pn. "544637".pn. "5454784".pn.	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/22 10:34
S65	22	(US-20050115673-\$ or US-20020020802-\$ or US-20010014520-\$ or US-20020048019-\$).did. or (US-6576922-\$ or US-5444637-\$ or US-5451784-\$ or US-6448094-\$ or US-5315145-\$ or US-6553277-\$ or US-5565681-\$ or US-6326794-\$ or US-5824602-\$ or US-6008132-\$ or US-5665253-\$ or US-6125529-\$ or US-5801386-\$ or US-6485988-\$ or US-6741945-\$ or US-6759253-\$).did. or (JP-10074481-\$ or EP-544637-\$).did.	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/08/22 11:50
S66	1	S65 and ((oxide or "SiO.sub.2") near7 (pore\$2 hole\$2 opening\$2))	USPAT	OR	OFF	2008/08/22 11:51
S67	11	((plasma charg\$3) near4 (monitor\$3 measur\$5)).ti. and ((oxide or "SiO.sub.2") near7 (pore\$2 hole\$2 opening\$2))	USPAT	OR	OFF	2008/08/22 11:54
S68	24	((plasma charg\$3) near4 (monitor\$3 measur\$5)).ab. and ((oxide or "SiO.sub.2") near7 (pore\$2 hole\$2 opening\$2))	USPAT	OR	OFF	2008/08/22 12:02
S69	15	S68 not S67	USPAT	OR	OFF	2008/08/22 12:02
S70	12	S69 and @ad< "20020326"	USPAT	OR	OFF	2008/08/22 12:03

S71	643	((plasma charg\$3) near4 (monitor\$3 measur\$5)) and ((oxide or "SiO.sub.2") near7 (pore\$2 hole\$2 opening\$2))	USPAT	OR	OFF	2008/08/22 12:05
S72	99	S71 and (ion\$2 near4 energy)	USPAT	OR	OFF	2008/08/22 12:05
S73	76	S72 and @ad< "20020326"	USPAT	OR	OFF	2008/08/22 12:05
S74	8	S73 not "16"	USPAT	OR	OFF	2008/08/22 12:06
S75	74	S73 not S68	USPAT	OR	OFF	2008/08/22 12:06
S76	73	S75 not S67	USPAT	OR	OFF	2008/08/22 12:06
S77	31	(itabashi near2 naoshi).in.	US-PGPUB; USPAT	OR	OFF	2008/12/07 17:59
S78	13	156/345.28.ccls. and ((plasma near6 (monitor\$4 evaluati\$3)) and (ion\$2 near8 ((energy mass) near4 (analyz\$4 measur\$5 monitor \$4))))	US-PGPUB; USPAT	OR	OFF	2008/12/07 18:09
S79	3	S78 and @ad< "20020326"	US-PGPUB; USPAT	OR	OFF	2008/12/07 18:10
S80	295	156/345.28.ccls.	US-PGPUB; USPAT	OR	OFF	2008/12/07 21:18
S81	123	S80 and @ad< "20020326"	US-PGPUB; USPAT	OR	OFF	2008/12/07 21:18
S82	158	S80 and @ad< "20030203"	US-PGPUB; USPAT	OR	OFF	2008/12/07 21:19
S83	51	S82 and (electrode\$2 near6 (sensor\$2 monitor\$4 probe \$2 measure\$5 detect\$4))	US-PGPUB; USPAT	OR	OFF	2008/12/07 21:21
S84	7883	((ion\$2 radical\$2 electron \$2) near6 analy\$5) and (electrode\$2 near6 (sensor \$2 monitor\$4 probe\$2 measure\$5 detect\$4))	US-PGPUB; USPAT	OR	OFF	2008/12/07 21:32
S85	4403	S84 and @ad< "20030203"	US-PGPUB; USPAT	OR	OFF	2008/12/07 21:32
S86	18	S85 and (156/345.\$2.ccls.)	US-PGPUB; USPAT	OR	OFF	2008/12/07 21:33
S87	280	((ion\$2 near3 energy) near6 (measure\$5 analy\$4 monitor \$4)) and (deep or (high adj aspect))	US-PGPUB; USPAT	OR	OFF	2008/12/08 08:22
S88	111	S87 and @ad< "20020326"	US-PGPUB; USPAT	OR	OFF	2008/12/08 08:23

S89	14	((ion\$2 near6 energy) near6 (measure\$5 analy\$4 monitor\$4)) same6 (deep or (high adj aspect))) and ((electrode\$2 conducti\$4) near7 (stack\$3 cascadi\$5 plural\$4))	US-PGPUB; USPAT	OR	OFF	2008/12/08 08:41
S90	14	((ion\$2 near6 energy) near6 (measure\$5 analy\$4 monitor\$4)) same6 (deep or (high adj aspect))) and ((electrode\$2 conducti\$4 conductor\$2) near7 (stack\$3 cascadi\$5 plural\$4))	US-PGPUB; USPAT	OR	OFF	2008/12/08 08:41
S91	2	S90 and @ad< "20020326"	US-PGPUB; USPAT	OR	OFF	2008/12/08 08:42
S92	904	(plasma near6 (monitor\$5 evaluat\$4 measure\$5)).ti. (plasma near6 (monitor\$5 evaluat\$4 measure\$5)).ab.	US-PGPUB; USPAT	OR	OFF	2008/12/08 08:46
S93	463	S92 and @ad< "20020326"	US-PGPUB; USPAT	OR	OFF	2008/12/08 08:46
S94	444	((ion\$2 near6 energy) near6 (measure\$5 analy\$4 monitor\$4)) and ((electrode\$2 conducti\$4 conductor\$2) near7 (stack\$3 cascadi\$5 plural\$4))	US-PGPUB; USPAT	OR	OFF	2008/12/08 08:47
S95	184	S94 and @ad< "20020326"	US-PGPUB; USPAT	OR	OFF	2008/12/08 08:48
S96	6	S93 and S95	US-PGPUB; USPAT	OR	OFF	2008/12/08 08:48
S97	2021	324/678.ccls. 257/48.ccls.	US-PGPUB; USPAT	OR	OFF	2008/12/08 08:56
S98	961	S97 and @ad< "20020326"	US-PGPUB; USPAT	OR	OFF	2008/12/08 08:56
S99	9	S98 and ((ion\$2 near6 energy) and ((electrode\$2 conducti\$4 conductor\$2) near4 (stack\$3 cascadi\$5 plural\$4)))	US-PGPUB; USPAT	OR	OFF	2008/12/08 08:59
S100	406	((ion\$2 near6 energy) near6 (measure\$5 analy\$4 monitor\$4)) and ((electrode\$2 conducti\$4 conductor\$2) near4 (stack\$3 cascadi\$5 plural\$4))	US-PGPUB; USPAT	OR	OFF	2008/12/08 09:01
S101	168	S100 and @ad< "20020326"	US-PGPUB; USPAT	OR	OFF	2008/12/08 09:02



S102	0	S98 and ((ion\$2 near6 energy) and ((electrode\$2 near8 wafer) near8 (potential voltage)))	US-PGPUB; USPAT	OR	OFF	2008/12/08 10:45
S103	507	((ion\$2 near6 energy) and ((electrode\$2 near8 wafer) near8 (potential voltage)))	US-PGPUB; USPAT	OR	OFF	2008/12/08 10:45
S104	818	((ion\$2 mass surface spectrum (charge\$2 adj particle\$2)) near6 (analy\$4 energy)) and ((electrode\$2 near8 wafer) near8 (potential voltage))	US-PGPUB; USPAT	OR	OFF	2008/12/08 10:48
S105	381	S104 and @ad<"20020326"	US-PGPUB; USPAT	OR	OFF	2008/12/08 10:48
S106	47	S105 and ((sensor\$2 monitor \$4 probe\$2 detector\$2) near8 (pattern\$4 resist etch \$3))	US-PGPUB; USPAT	OR	OFF	2008/12/08 10:49
S107	47	S105 and ((sensor\$2 monitor \$4 probe\$2 detector\$2) near8 (pattern\$4 resist etch \$3))	US-PGPUB; USPAT	OR	OFF	2008/12/08 11:36
S108	53	((ion\$2 mass surface spectrum (charge\$2 adj particle\$2)) near6 (analy\$4 energy)) and ((electrode\$2 near8 wafer) near8 equal\$4 same (potential voltage))	US-PGPUB; USPAT	OR	OFF	2008/12/08 11:52
S109	284	S92 and (((sensor\$2 monitor \$4 probe\$2 detector\$2) near8 (pattern\$4 resist etch \$3)) and ((electrode with (voltage potential)) with equal\$4 (wafer substrate)))	US-PGPUB; USPAT	OR	OFF	2008/12/08 11:57
S110	0	S92 and (((sensor\$2 monitor \$4 probe\$2 detector\$2) near8 (pattern\$4 resist etch \$3)) and ((electrode with (voltage potential)) with equal\$4 with (wafer substrate)))	US-PGPUB; USPAT	OR	OFF	2008/12/08 11:57
S111	0	plasma and (((sensor\$2 monitor\$4 probe\$2 detector \$2) near8 (pattern\$4 resist etch\$3)) and ((electrode with (voltage potential)) with equal\$4 with (wafer substrate)))	US-PGPUB; USPAT	OR	OFF	2008/12/08 11:58

S112	0	((sensor\$2 monitor\$4 probe\$2 detector\$2) near8 (pattern\$4 resist etch\$3)) and ((electrode with (voltage potential)) with equal\$4 with (wafer substrate)))	US-PGPUB; USPAT	OR	OFF	2008/12/08 11:58
S113	1	"6423242".pn.	US-PGPUB; USPAT	OR	OFF	2008/12/08 12:13
S114	494	plasma and (((sensor\$2 monitor\$4 probe\$2 detector\$2) near8 (pattern\$4 resist etch\$3)) and (electrode near8 connect\$3 near8 (wafer substrate)))	US-PGPUB; USPAT	OR	OFF	2008/12/08 13:29
S115	194	S114 and @ad<"20020326"	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/12/08 13:29
S116	155	plasma and (((sensor\$2 monitor\$4 probe\$2 detector\$2) near8 (pattern\$4 resist etch\$3)) and (electrode near8 connect\$3 near8 wafer))	US-PGPUB; USPAT	OR	OFF	2008/12/08 13:30
S117	60	S116 and @ad<"20020326"	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/12/08 13:31
S118	562	hassanzad\$4.xa hassanzad\$4.xp.	US-PGPUB; USPAT	OR	OFF	2008/12/09 19:39
S119	29	S118 and ((plasma near6 (monitor\$4 evaluat\$4)) and (sensor\$2 probe\$2 detector\$2))	US-PGPUB; USPAT	OR	OFF	2008/12/09 19:41
S120	0	S118 and (MIT.as. and (sensor\$2 probe\$2 detector\$2))	US-PGPUB; USPAT	OR	OFF	2008/12/09 19:48
S121	0	S118 and MIT.as.	US-PGPUB; USPAT	OR	OFF	2008/12/09 19:49
S122	0	S118 and Massachussets.as.	US-PGPUB; USPAT	OR	OFF	2008/12/09 19:49
S123	73	S118 and plasma and monitor\$4 and (sensor\$2 probe\$2 detector\$2)	US-PGPUB; USPAT	OR	OFF	2008/12/09 19:50
S124	48	S123 not S119	US-PGPUB; USPAT	OR	OFF	2008/12/09 19:50
S125	1	S118 and (Applied near4 Science near4 Technology).as.	US-PGPUB; USPAT	OR	OFF	2008/12/09 19:55

S126	14	((plasma near7 (monitor\$4 evaluat\$4 in-situ)) and ((sensor42 probe42 detector \$2 monitor\$4) same4 (pattern\$4 same (electrode \$2 conduct\$4))))).clm.	US-PGPUB; USPAT	OR	OFF	2008/12/09 20:00
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12/ 9/ 2008 11:01:42 PM

H:\ Workspaces\ Plas\_monitor\_10501351A.wsp